



PATENT  
ATTORNEY DOCKET NO. 07977/052001/US3053

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Hisashi Ohtani et al. Art Unit: 1765  
Serial No.: 08/690,747 Examiner: R. Kunemund  
Filed : August 1, 1996  
Title : METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE

**Box AF**  
Assistant Commissioner for Patents  
Washington, DC 20231

AMENDMENT

Sir:

In response to the Official Action dated April 7, 1999, paper no. 9 in the above-referenced case, kindly amend the above-referenced application as follows:

In the Claims

Please amend the claims as follows.

1. (Amended) A method for manufacturing a semiconductor device comprising the steps of:

forming a non-single crystalline semiconductor film to become at least a channel forming region on an insulating surface;

patterning said semiconductor film into a patterned semiconductor film having peripheral portions;

Date of Deposit

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated above and is addressed to the Assistant Commissioner for Patents, Washington, D.C. 20231.

Deborah Dear